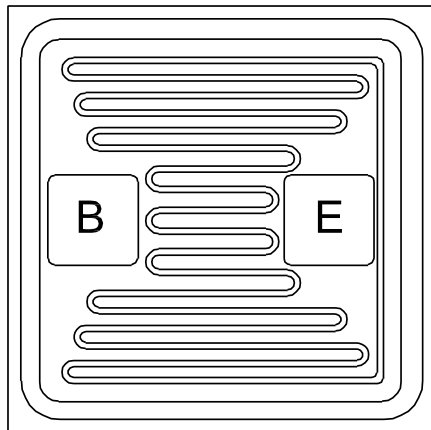


**PROCESS CP318V**  
**Small Signal Transistor**  
NPN - High Voltage Transistor Chip

**PROCESS DETAILS**

Process	EPITAXIAL PLANAR
Die Size	26 x 26 MILS
Die Thickness	7.1 MILS $\pm$ 0.6 MILS
Base Bonding Pad Area	5.5 x 5.5 MILS
Emitter Bonding Pad Area	5.5 x 5.5 MILS
Top Side Metalization	Al Si - 17,000Å
Back Side Metalization	Au - 12,000Å

**GEOMETRY**



R0

BACKSIDE COLLECTOR

**GROSS DIE PER 5 INCH WAFER**

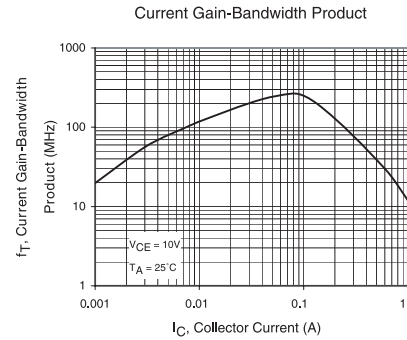
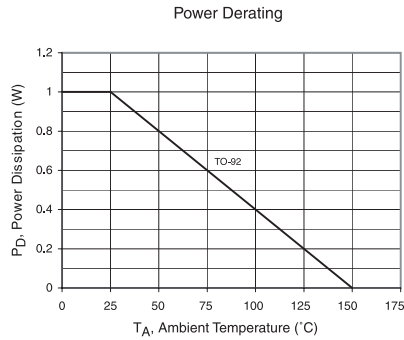
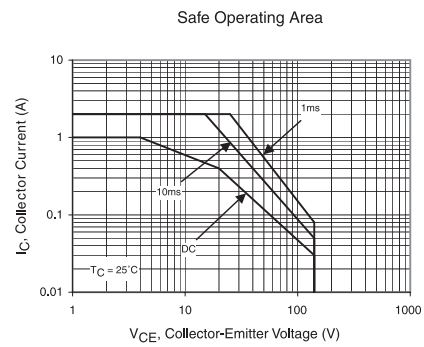
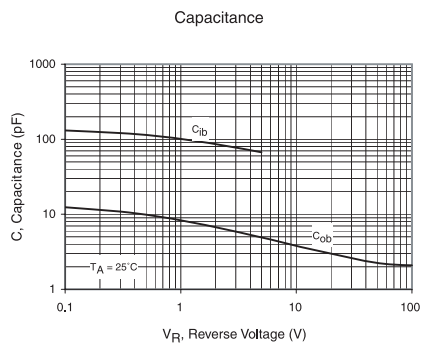
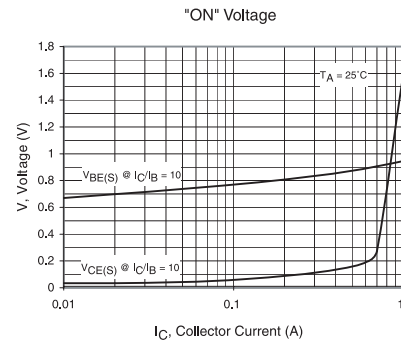
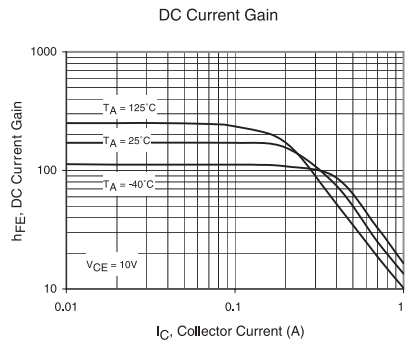
25,536

**PRINCIPAL DEVICE TYPES**

MPS455

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